U.S. PATENT DOCUMENTS								
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE (IF APPROPRIATE)		
Ye-	4502914	03/05/85	Trumpp et al.	438	424			
<u>Un</u>	5087586	02/11/92	Chan et al.	438	429	<u> </u>		
<u>h</u>	5169491	12/08/92	Doan	438	693	-		
Vn	5191509	03/02/93	Wen	257	304			
Va	5302233	04/12/94	Kim et al.	438	692			
Va	5366590	11/22/94	Kadomura	438	723			
<u>M</u>	5470783	11/28/95	Chiu et al.	438	446			
<u>Vh</u>	5530293	06/25/96	Cohen et al.	257	752			

EXAMINER INITIAL	OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)				
⅓	 	Kirk-Othmer, Encyclopedia of Chemical Technology, Second Completely Revised Edition, Vol. II, 1966. pp. 791-792.			
		Silicon Processing for the VLSI ERA, Isolation Technologies for Integrated Circuits, Vol. II, Ch. 2, pp. 12-83			

EXAMINER HUNG K. VU	DATE CONSIDERED 08/02/98
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